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NEWS 10 Jun 10 MEDLINE Reload

NEWS 11 Jun 10 PCTFULL has been reloaded

NEWS 12 Jul 02 FOREGE no longer contains STANDARDS file segment

NEWS 13 Jul 22 USAN to be reloaded July 28, 2002; saved answer sets no longer valid

NEWS 14 Jul 29 Enhanced polymer searching in REGISTRY

NEWS 15 Jul 30 NETFIRST to be removed from STN

NEWS 16 Aug 08 CANCERLIT reload

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NEWS 18 Aug 08 NTIS has been reloaded and enhanced

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NEWS 20 Aug 19 IFIPAT, IFICDB, and IFIUDB have been reloaded

NEWS 21 Aug 19 The MEDLINE file segment of TOXCENTER has been reloaded

NEWS 22 Aug 26 Sequence searching in REGISTRY enhanced

NEWS 23 Sep 03 JAPIO has been reloaded and enhanced

NEWS EXPRESS February 1 CURRENT WINDOWS VERSION IS V6.0d, CURRENT MACINTOSH VERSION IS V6.0a(ENG) AND V6.0Ja(JP), AND CURRENT DISCOVER FILE IS DATED 05 FEBRUARY 2002

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FILE 'HOME' ENTERED AT 11:46:17 ON 09 SEP 2002

=> fil casreact

COST IN U.S. DOLLARS

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FULL ESTIMATED COST

FILE 'CASREACT' ENTERED AT 11:46:28 ON 09 SEP 2002 USE IS SUBJECT TO THE TERMS OF YOUR CUSTOMER AGREEMENT COPYRIGHT (C) 2002 AMERICAN CHEMICAL SOCIETY (ACS)

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FILE CONTENT:1974 - 8 Sep 2002 VOL 137 ISS 10

Some records from 1974 to 1991 are derived from the ZIC/VINITI data file and provided by InfoChem.

This file contains CAS Registry Numbers for easy and accurate substance identification.

Crossover limits have been increased. See HELP RNCROSSOVER for details.

Structure search limits have been raised. See HELP SLIMIT for the new, higher limits.

=>

Uploading 09961347b.str

L1 STRUCTURE UPLOADED

=> d

L1 HAS NO ANSWERS

L1 STR



G1 O, S, Po, Se, Te

Structure attributes must be viewed using STN Express query preparation.

=> s 11

SAMPLE SEARCH INITIATED 11:46:46 FILE 'CASREACT'
SCREENING COMPLETE - 13472 REACTIONS TO VERIFY FROM

672 DOCUMENTS

37.1% DONE 5000 VERIFIED

1639 HIT RXNS

50 DOCS

Examiner Anderson 703-605-1157

09961347 Page 3 09/09/2002

INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)

SEARCH TIME: 00.00.02

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*

BATCH \*\*COMPLETE\*\*

PROJECTED VERIFICATIONS: 262630 TO 276250 PROJECTED ANSWERS: 11722 TO 14748

50 SEA SSS SAM L1 ( 1639 REACTIONS) T.2

=> s l1 full

FULL SEARCH INITIATED 11:46:52 FILE 'CASREACT' SCREENING COMPLETE - 242717 REACTIONS TO VERIFY FROM 12870 DOCUMENTS

89.1% DONE 216373 VERIFIED 211045 HIT RXNS ( 1 INCOMP) 11695 DOCS

98.9% DONE 240069 VERIFIED 234234 HIT RXNS ( 1 INCOMP) 12306 DOCS

100.0% DONE 242717 VERIFIED 236874 HIT RXNS ( 1 INCOMP) 12386 DOCS

SEARCH TIME: 00.00.44

L3 12386 SEA SSS FUL L1 (236874 REACTIONS)

=>

Uploading 09961347b.str

L4 STRUCTURE UPLOADED

=> d

L4 HAS NO ANSWERS

STR



G1 O, S, Po, Se, Te

Structure attributes must be viewed using STN Express query preparation.

=> s 14

SAMPLE SEARCH INITIATED 11:47:49 FILE 'CASREACT'

SCREENING COMPLETE - 1220 REACTIONS TO VERIFY FROM 222 DOCUMENTS

50 DOCS

230 HIT RXNS 100.0% DONE 1220 VERIFIED INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*

BATCH \*\*COMPLETE\*\*

PROJECTED VERIFICATIONS: 22309 TO 26491

PROJECTED ANSWERS: 3390 TO 5130

50 SEA SSS SAM L4 ( 230 REACTIONS)

Examiner Anderson 703-605-1157

=> s 14 full FULL SEARCH INITIATED 11:47:54 FILE 'CASREACT' SCREENING COMPLETE - 25432 REACTIONS TO VERIFY FROM 4279 DOCUMENTS 100.0% DONE 25432 VERIFIED 24308 HIT RXNS SEARCH TIME: 00.00.03 4039 DOCS L6 4039 SEA SSS FUL L4 ( 24308 REACTIONS) => s 16 and pyridine 16818 PYRIDINE 2730 PYRIDINES 17675 PYRIDINE (PYRIDINE OR PYRIDINES) L7 289 L6 AND PYRIDINE => s 17 and benzyl trichloromethyl sulfide 20819 BENZYL 2 BENZYLS 20819 BENZYL (BENZYL OR BENZYLS) 886 TRICHLOROMETHYL 8490 SULFIDE 3602 SULFIDES 9325 SULFIDE (SULFIDE OR SULFIDES) 1 BENZYL TRICHLOROMETHYL SULFIDE (BENZYL (W) TRICHLOROMETHYL (W) SULFIDE) Г8 1 L7 AND BENZYL TRICHLOROMETHYL SULFIDE

=> d

# 09961347 Page 5 09/09/2002

L8 ANSWER 1 OF 1 CASREACT COPYRIGHT 2002 ACS

RX(1) OF 11

Cl<sub>3</sub>C-S-CH<sub>2</sub>-Ph

Olah's reagent

F<sub>3</sub>C-S-CH<sub>2</sub>-Ph

REF: Eur. Pat. Appl., 729930, 04 Sep 1996 NOTE: 0.degree. to room temp.

Examiner Anderson 703-605-1157

```
=> s 16 and benzyl trichloromethyl sulfide
         20819 BENZYL
             2 BENZYLS
         20819 BENZYL
                 (BENZYL OR BENZYLS)
          886 TRICHLOROMETHYL
          8490 SULFIDE
          3602 SULFIDES
          9325 SULFIDE
                 (SULFIDE OR SULFIDES)
             1 BENZYL TRICHLOROMETHYL SULFIDE
                 (BENZYL (W) TRICHLOROMETHYL (W) SULFIDE)
             1 L6 AND BENZYL TRICHLOROMETHYL SULFIDE
L9
=> s 17 and HF
          1858 HF
            10 HFS
          1868 HF
                (HF OR HFS)
            10 L7 AND HF
L10
=> d 110 1-10
```

RX(2) OF 52

REF: Journal of Labelled Compounds & Radiopharmaceuticals, 44(12), NOTE: KEY STEP

L10 ANSWER 3 OF 10 CASREACT COPYRIGHT 2002 ACS

RX (6) OF 61

REF: Journal of Combinatorial Chemistry, 3(3), 312-318, 2001 NOTE: resin supported reaction

L10 ANSWER 2 OF 10 CASREACT COPYRIGHT 2002 ACS

RX(1) OF 36

Cl<sub>3</sub>C-S-CH<sub>2</sub>-Ph 1. HF, Pyridine F<sub>3</sub>C-S-CH<sub>2</sub>-Ph (step 1) 95%

REF: U.S., 6316636, 13 Nov 2001

L10 ANSWER 4 OF 10 CASREACT COPYRIGHT 2002 ACS

RX (7) OF 15

REF: Bulletin of the Chemical Society of Japan, 73(2), 471-484; 2000 NOTE: ANALOGUES HAVE SIMILAR REACTION

#### 09961347 Page 8 09/09/2002

L10 ANSWER 5 OF 10 CASREACT COPYRIGHT 2002 ACS

REF: Jpn. Kokai Tokkyo Koho, 11049759, 23 Feb 1999, Heisei

L10 ANSWER 7 OF 10 CASREACT COPYRIGHT 2002 ACS

REF: Eur. Pat. Appl., 729930, 04 Sep 1996 NOTE: 0.degree. to room temp. L10 ANSWER 6 OF 10 CASREACT COPYRIGHT 2002 ACS

RX(1) OF 9

L10 ANSWER 8 OF 10 CASREACT COPYRIGHT 2002 ACS

RX(2) OF 13

 $\begin{picture}(10,0) \put(0,0){\line(0,0){150}} \put(0,0){\line(0,0){15$ 

C13C-0-CHF2

REF: Eur. Pat. Appl., 562858, 29 Sep 1993 NOTE: .ltoreq.50.degree., photochem., vapor phase, trichloro product formation inhibited by oxygen

### 09961347 Page 9 09/09/2002

L10 ANSWER 9 OF 10 CASREACT COPYRIGHT 2002 ACS

L10 ANSWER 10 OF 10 CASREACT COPYRIGHT 2002 ACS

Examiner Anderson 703-605-1157

(PEROXIDE OR PEROXIDES)

4068 PEROXIDE 789 PEROXIDES 4303 PEROXIDE

40 L6 AND PEROXIDE

L15

=> d 114 1-59

### 09961347 Page 11 09/09/2002

L14 ANSWER 1 OF 59 CASREACT COPYRIGHT 2002 ACS

L14 ANSWER 3 OF 59 CASREACT COPYRIGHT 2002 ACS

RX(1) OF 36 
$$\frac{\text{Cl}_3\text{C-S-CH}_2\text{-Ph}}{(\text{step 1})} \quad \frac{1. \text{ HF, Pyridine}}{2. \text{ Water, CH2C12}} \quad \frac{\text{F}_3\text{C-S-CH}_2\text{-Ph}}{\text{951}}$$
 REF: U.S., 6316636, 13 Nov 2001

L14 ANSWER 2 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Journal of Labelled Compounds & Radiopharmaceuticals, 44(12), 815-829, 2001
NOTE: KEY STEP

L14 ANSWER 4 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Bioorganic & Medicinal Chemistry, 9(3), 665-675; 2001

REF: Journal of Combinatorial Chemistry, 3(3), 312-318, 2001 NOTE: resin supported reaction

L14 ANSWER 7 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Journal of Fluorine Chemistry, 103(1), 81-84; 2000 NOTE: alternate higher-yield procedure shown

L14 ANSWER 6 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Journal of Fluorine Chemistry, 106(1), 25-34; 2000 NOTE: author caution of exothermic reaction

L14 ANSWER 8 OF 59 CASREACT COPYRIGHT 2002 ACS

RX(7) OF 15

REF: Bulletin of the Chemical Society of Japan, 73(2), 471-484; 2000 NOTE: ANALOGUES HAVE SIMILAR REACTION

L14 ANSWER 10 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Journal of Fluorine Chemistry, 94(1), 1-5; 1999 NOTE: safety: HF evolved during reaction

L14 ANSWER 11 OF 59 CASREACT COPYRIGHT 2002 ACS

RX (2) OF 3

REF: Jpn. Kokai Tokkyo Koho, 11049759, 23 Feb 1999, Heisei

L14 ANSWER 12 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Fr. Demande, 2763940, 04 Dec 1998

## 09961347 Page 14 09/09/2002

L14 ANSWER 13 OF 59 CASREACT COPYRIGHT 2002 ACS

Me- (CH<sub>2</sub>)<sub>4</sub>-Me +

RX (1) OF 1

REF: Chemical Communications (Cambridge), (20), 2263-2264; 1998

L14 ANSWER 15 OF 59 CASREACT COPYRIGHT 2002 ACS

RX (1) OF 1

REF: Journal of Organic Chemistry, 62(18), 6160-6163, 1997 NOTE: FINAL STAGES ARE DECARBOXYLATION OF INTERMEDIATE PROPION L14 ANSWER 14 OF 59 CASREACT COPYRIGHT 2002 ACS

RX (1) OF 9

REF: Journal of Fluorine Chemistry, 91(1), 9-12; 1998 NOTE: electrochem.

L14 ANSWER 16 OF 59 CASREACT COPYRIGHT 2002 ACS

RX(1) OF 9

| S | Olah's reagent, | F3C-O-(CH2)15-Me | MeS-C-O-(CH2)15-Me | MeS-C-O

Examiner Anderson 703-605-1157

### 09961347 Page 15 09/09/2002

L14 ANSWER 17 OF 59 CASREACT COPYRIGHT 2002 ACS

CF2 BF3, IC1, HF F3C-O-CF2-CF2-I 841

REF: Journal of Organic Chemistry, 61(26), 9605-9607, 1996

NOTE: regioselective

L14 ANSWER 18 OF 59 CASREACT COPYRIGHT 2002 ACS

Cl<sub>3</sub>C-S-CH<sub>2</sub>-Ph Olah's reagent F<sub>3</sub>C-S-CH<sub>2</sub>-Ph

REF: Eur. Pat. Appl., 729930, 04 Sep 1996 NOTE: O.degree. to room temp.

L14 ANSWER 19 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Zeitschrift fuer Naturforschung, B: Chemical Sciences, 51(7), 1015-1021, 1996
NOTE: ANALOGOUS REACTION WITH PF6 COUNTERION GIVES SIMILAR RESULTS

L14 ANSWER 20 OF 59 CASREACT COPYRIGHT 2002 ACS

RX(2) OF 3

REF: U.S., 5481028, 02 Jan 1996

## 09961347 Page 16 09/09/2002

L14 ANSWER 21 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Ger., 4332383, 27 Apr 1995

L14 ANSWER 22 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: U.S., 5382704, 17 Jan 1995 NOTE: METAL TUBE, 150 .DEGREES. FOR 8 H

L14 ANSWER 23 OF 59 CASREACT COPYRIGHT 2002 ACS

L14 ANSWER 24 OF 59 CASREACT COPYRIGHT 2002 ACS

RX (1) OF 1

REF: Jpn. Kokai Tokkyo Koho, 06298694, 25 Oct 1994, Heisei

80% REF: Inorganic Chemistry, 33(24), 5463-70; 1994

L14 ANSWER 27 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Bull. Korean Chem. Soc., 14(4), 424-5; 1993

L14 ANSWER 26 OF 59 CASREACT COPYRIGHT 2002 ACS

RX(3) OF 6

REF: Bulletin de la Societe Chimique de France, 131(1), 95-104; 1994

114 ANSWER 28 OF 59 CASREACT COPYRIGHT 2002 ACS

C13C-0-CHF2

REF: Eur. Pat. Appl., 562858, 29 Sep 1993 NOTE: .ltoreq.50.degree., photochem., vapor phase, trichloro product formation inhibited by oxygen

### 09961347 Page 18 09/09/2002

L14 ANSWER 29 OF 59 CASREACT COPYRIGHT 2002 ACS

RX (1) OF 21

REF: J. Labelled Compd. Radiopharm., 33(6), 483-91; 1993

L14 ANSWER 30 OF 59 CASREACT COPYRIGHT 2002 ACS

L14 ANSWER 31 OF 59 CASREACT COPYRIGHT 2002 ACS

C13C-0-CHF2

REF: U.S., 5196600, 23 Mar 1993 NOTE: photochem., product ratio ? on reaction conditions, gas phase

L14 ANSWER 32 OF 59 CASREACT COPYRIGHT 2002 ACS

RX(1) OF 3

C1 #86%
REF: Jpn. Kokai Tokkyo Koho, 05000988, 08 Jan 1993, Heisei

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L14 ANSWER 33 OF 59 CASREACT COPYRIGHT 2002 ACS

RX(4) OF 8

S=C=S SF4, HF, C12, F3C-S-S-CF3 + F3C-S-S-S-CF3 901 901 REF: Zh. Org. Khim., 28(5), 892-900; 1992

L14 ANSWER 34 OF 59 CASREACT COPYRIGHT 2002 ACS

F3C-S-SH CF3SC1 F3C-S-S-S-CF3

REF: Inorg. Chem., 31(20), 4147-50; 1992

L14 ANSWER 35 OF 59 CASREACT COPYRIGHT 2002 ACS

L14 ANSWER 36 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Inorg. Chem., 31(2), 225-7; 1992

## 09961347 Page 20 09/09/2002

L14 ANSWER 37 OF 59 CASREACT COPYRIGHT 2002 ACS  $\label{eq:rx} {\rm RX}\,(2) \mbox{ OF } 2$ 

REF: Fr. Demande, 2647106, 23 Nov 1990

L14 ANSWER 38 OF 59 CASREACT COPYRIGHT 2002 ACS

RX (2) OF 3

REF: J. Fluorine Chem., 49(2), 225-9; 1990

L14 ANSWER 39 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Ger. (East), 274820, 03 Jan 1990

L14 ANSWER 40 OF 59 CASREACT COPYRIGHT 2002 ACS

L14 ANSWER 42 OF 59 CASREACT COPYRIGHT 2002 ACS RX(18) OF 25 - REACTION DIAGRAM NOT AVAILABLE

REF: Carbohydr. Res., 187(1), 67-92; 1989

L14 ANSWER 43 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Eur. Pat. Appl., 196529, 08 Oct 1986

L14 ANSWER 44 OF 59 CASREACT COPYRIGHT 2002 ACS

RX(1) OF 52

F-CCl<sub>2</sub>-S-C1

Me2CO

Me C-CH<sub>2</sub>-S-CCl<sub>2</sub>-F

631 631
REF: J. Fluorine Chem., 40(2-3), 365-73; 1988

REF: J. Org. Chem., 54(7), 1664-8; 1989

L14 ANSWER 47 OF 59 CASREACT COPYRIGHT 2002 ACS

L14 ANSWER 46 OF 59 CASREACT COPYRIGHT 2002 ACS

L14 ANSWER 48 OF 59 CASREACT COPYRIGHT 2002 ACS

## 09961347 Page 23 09/09/2002

L14 ANSWER 49 OF 59 CASREACT COPYRIGHT 2002 ACS RX(14) OF 51

REF: J. Am. Chem. Soc., 109(7), 2049-56; 1987

L14 ANSWER 51 OF 59 CASREACT COPYRIGHT 2002 ACS

F-CCl<sub>2</sub>-5-Cl <u>Acetophenone</u> Ph-C-CH<sub>2</sub>-5-CCl<sub>2</sub>-F
REF: Ger. Offen., 3341515, 30 May 1985

L14 ANSWER 50 OF 59 CASREACT COPYRIGHT 2002 ACS

RX(5) OF 25

$$\begin{array}{c}
S \\
F-G-S-CF_3
\end{array}
\xrightarrow{SbF5, HF}
\xrightarrow{F_3G-S}
S \xrightarrow{F_3F-S-CF_3}
F \xrightarrow{F-Sb5+F-S}$$

REF: Chem. Ber., 120(3), 429-33; 1987

L14 ANSWER 52 OF 59 CASREACT COPYRIGHT 2002 ACS

RX (3) OF 9

F-CCl<sub>2</sub>-S-Cl <u>Acetophenone</u> Ph-C-CH<sub>2</sub>-S-CCl<sub>2</sub>-F
REF: Ger. Offen., 3341516, 30 May 1985

F<sub>3</sub>C-Se-Cl AgF F<sub>3</sub>C-Se-Se-CF<sub>3</sub>

REF: Z. Naturforsch., B: Anorg. Chem., Org. Chem., 39B(7), 897-902; 1984

L14 ANSWER 54 OF 59 CASREACT COPYRIGHT 2002 ACS

RX(1) OF 4

REF: Ger. Offen., 3304203, 09 Aug 1984

L14 ANSWER 55 OF 59 CASREACT COPYRIGHT 2002 ACS

RX(3) OF 3

REF: Eur. Pat. Appl., 110690, 13 Jun 1984

L14 ANSWER 56 OF 59 CASREACT COPYRIGHT 2002 ACS

REF: Ger. Offen., 3232624, 22 Mar 1984

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L14 ANSWER 57 OF 59 CASREACT COPYRIGHT 2002 ACS

L14 ANSWER 58 OF 59 CASREACT COPYRIGHT 2002 ACS

L14 ANSWER 59 OF 59 CASREACT COPYRIGHT 2002 ACS

09961347 Page 26 09/09/2002

=> d 115 1-40

RX (10) OF 11

Na 80%

REF: Journal of Organic Chemistry, 66(20), 6745-6755; 2001

L15 ANSWER 3 OF 40 CASREACT COPYRIGHT 2002 ACS

L15 ANSWER 2 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: Jpn. Kokai Tokkyo Koho, 2001220376, 14 Aug 2001 NOTE: adding Br2 over 5 h at 60-70.degree.; 65-75.degree. for 10 h

L15 ANSWER 4 OF 40 CASREACT COPYRIGHT 2002 ACS

## 09961347 Page 28 09/09/2002

L15 ANSWER 5 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: Journal of Organic Chemistry, 65(24), 8317-8325; 2000 NOTE: regioselective

L15 ANSWER 7 OF 40 CASREACT COPYRIGHT 2002 ACS

RX(2) OF 3

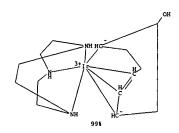
$$\overset{\circ}{\underset{F}{\longleftrightarrow}} \overset{\circ}{\underset{F}{\longleftrightarrow}} \xrightarrow{\text{COF2, CsF}} \overset{\circ}{\underset{F-C-0-0-CF_3}{\longleftrightarrow}} \overset{\circ}{\underset{F-C-0-0-CF_2-0-0-CF_3}{\longleftrightarrow}} \overset{\circ}{\underset{F}{\longleftrightarrow}}$$

F-C-O-O-CF<sub>2</sub>-O-O-CF<sub>2</sub>-O-O-CF<sub>3</sub>

REF: Chemical Communications (Cambridge), (17), 1671-1672, 1999

NOTE: gas-phase reactants over solid catalyst in sealed tube

L15 ANSWER 6 OF 40 CASREACT COPYRIGHT 2002 ACS



REF: Chemical Communications (Cambridge), (17), 1681-1682; 2000 NOTE: N-Me analog also used; other oxidn. agents gave no result

L15 ANSWER 8 OF 40 CASREACT COPYRIGHT 2002 ACS

RX(1) OF 34

Eto-C-CH<sub>2</sub>-CH<sub>2</sub>-S-G-CF<sub>3</sub> Cyclohexene, CH2C12

REF: Tetrahedron, 55(26), 8065-8074; 1999 NOTE: stereoselective

REF: Organometallics, 17(23), 4976-4982; 1998

RX(2) OF 7

L15 ANSWER 10 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: Journal of the Chemical Society, Perkin Transactions 1: Organic and Bio-Organic Chemistry, (10), 1643-1656; 1998

L15 ANSWER 11 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: PCT Int. Appl., 9700859, 09 Jan 1997

L15 ANSWER 12 OF 40 CASREACT COPYRIGHT 2002 ACS

RX (6) OF 6

REF: Eur. Pat. Appl., 700885, 13 Mar 1996 NOTE: one-pot reaction

### 09961347 Page 30 09/09/2002

L15 ANSWER 13 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: Journal of Medicinal Chemistry, 39(9), 1885-97; 1996

L15 ANSWER 15 OF 40 CASREACT COPYRIGHT 2002 ACS

 $\begin{array}{c} \mathsf{CF_2-O-CF_2-CF_2-O-CF_2-CF_2-O-CF_3} \\ \\ \mathsf{CF_2-O-CF_2-CF_2-O-CF_2-CF_2-O-CF_3} \\ \\ \mathsf{CF_2-O-CF_2-CF_2-O-CF_2-CF_2-O-CF_3} \end{array}$ 

REF: Izvestiya Akademii Nauk, Seriya Khimicheskaya, (10), 1789-92, 1994 NOTE: THERMAL L15 ANSWER 14 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: PCT Int. Appl., 9513284, 18 May 1995

L15 ANSWER 16 OF 40 CASREACT COPYRIGHT 2002 ACS

> F-C-503<sup>-</sup> | | 72%

REF: Tetrahedron Letters, 35(43), 8015-18; 1994

RX(35) OF 40 OF 
$$F = S - CF_3$$
 + Me<sub>3</sub>Si - O - CH<sub>2</sub> - CF<sub>2</sub> - CF<sub>2</sub> - CH<sub>2</sub> - O - SiMe<sub>3</sub> 1. CsF, MeCN, (step 2)

808 REF: Inorganic Chemistry, 33(24), 5463-70; 1994

L15 ANSWER 19 OF 40 CASREACT COPYRIGHT 2002 ACS

79% REF: Jpn. Kokai Tokkyo Koho, 05170689, 09 Jul 1993, Heisei NOTE: 40.degree.

L15 ANSWER 18 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: Journal of Fluorine Chemistry, 68(1), 63-6; 1994 NOTE: stereoselective

L15 ANSWER 20 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: J. Org. Chem., 58(7), 1762-5; 1993

## 09961347 Page 32 09/09/2002

L15 ANSWER 21 OF 40 CASREACT COPYRIGHT 2002 ACS

RX(4) OF 8
S=C=S
SF4, HF, C12
F3C-S-S-CF3
901
901

REF: Zh. Org. Khim., 28(5), 892-900; 1992

L15 ANSWER 22 OF 40 CASREACT COPYRIGHT 2002 ACS

RX (6) OF 69

REF: J. Org. Chem., 57(20), 5301-12; 1992

L15 ANSWER 23 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: Eur. Pat. Appl., 458684, 27 Nov 1991

L15 ANSWER 24 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: J. Am. Chem. Soc., 113(6), 2242-6: 1991

## 09961347 Page 33 09/09/2002

L15 ANSWER 25 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: J. Am. Chem. Soc., 113(5), 1730-6; 1991 NOTE: photochem.

L15 ANSWER 27 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: Carbohydr. Res., 200,, 377-89; 1990

L15 ANSWER 26 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: Ger. Offen., 3836149, 10 May 1990

L15 ANSWER 28 OF 40 CASREACT COPYRIGHT 2002 ACS

RX(1) OF 7

REF: J. Fluorine Chem., 47(1), 131-6; 1990 NOTE: TAUTOMERIC REACTANT ALSO PRESENT

### 09961347 Page 34 09/09/2002

L15 ANSWER 29 OF 40 CASREACT COPYRIGHT 2002 ACS RX(1) OF 1

REF: Ger. Offen., 3712318, 20 Oct 1988

L15 ANSWER 31 OF 40 CASREACT COPYRIGHT 2002 ACS

RX(18) OF 393

REF: J. Org. Chem., \$3(13), 3098-104; 1988

L15 ANSWER 30 OF 40 CASREACT COPYRIGHT 2002 ACS

Meo-C-CMe

C12

C13C-O-C-O-CCl3

REF: Bul. Stint. Teh. Inst. Politeh. "Traian Vuia" Timisoara, Ser. Chim., 32(1-2), 53-8, 1987

NOTE: photochem.

115 ANSWER 32 OF 40 CASREACT COPYRIGHT 2002 ACS

F<sub>3</sub>C-O-O-CF<sub>3</sub> CF2:CC12 F<sub>3</sub>C-O-CF<sub>2</sub>-CCl<sub>2</sub>-O-O-CF<sub>3</sub> +

F3C-0-CF2-CCl2-CF2-CCl2-0-0-CF3 +

 ${\tt F_3C-O-CF_2-CCl_2-CF_2-CCl_2-CF_2-CCl_2-O-O-CF_3} \quad + \quad$ 

 ${\tt F_3C-O-CF_2-CCl_2-CF_2-CCl_2-CF_2-CCl_2-CF_2-CCl_2-O-O-CF_3}$ REF: J. Fluorine Chem., 37(1), 47-51; 1987 NOTE: gas phase

### 09961347 Page 35 09/09/2002

L15 ANSWER 33 OF 40 CASREACT COPYRIGHT 2002 ACS

RX (54) OF 72

498

REF: J. Chem. Soc., Perkin Trans. 1, (12), 2081-90; 1986
NOTE: photochem.

L15 ANSWER 34 OF 40 CASREACT COPYRIGHT 2002 ACS

RX (18) OF 314

L15 ANSWER 35 OF 40 CASREACT COPYRIGHT 2002 ACS

RX (1) OF 13

L15 ANSWER 36 OF 40 CASREACT COPYRIGHT 2002 ACS

RX(1) OF 3

Na REF: Zh. Vses. Khim. O-va., 29(1), 113-14; 1984

### 09961347 Page 36 09/09/2002

L15 ANSWER 37 OF 40 CASREACT COPYRIGHT 2002 ACS

RX(6) OF 34  $F_2C=N-CF_2-CF_2-C1 + F_3C-O-OH$   $\longrightarrow$ 

F3C-0-0-CF2-NH-CF2-CF2-C1

REF: J. Org. Chem., 48(25), 4844-7; 1983

L15 ANSWER 38 OF 40 CASREACT COPYRIGHT 2002 ACS

RX(1) OF 40

F<sub>3</sub>C-C-O O F<u>3CSO2H, Benzene</u>

REF: J. Fluorine Chem., 20(5), 695-8; 1982

L15 ANSWER 39 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: Khimiya i Tekhnol. Elementoorgan. Poluproduktov. i Polimerov, Volgograd, 92-7; 1981

L15 ANSWER 40 OF 40 CASREACT COPYRIGHT 2002 ACS

REF: 2h. Org. Khim., 17(8), 1652-7; 1981

=> fil caplus COST IN U.S. DOLLARS

SINCE FILE TOTAL ENTRY SESSION 464.31 464.52

FULL ESTIMATED COST

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FILE COVERS 1907 - 9 Sep 2002 VOL 137 ISS 11 FILE LAST UPDATED: 8 Sep 2002 (20020908/ED)

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=> s fluorocarbon

12055 FLUOROCARBON

3750 FLUOROCARBONS

L16 13705 FLUOROCARBON

(FLUOROCARBON OR FLUOROCARBONS)

=> s 116 and process

1708883 PROCESS

1096956 PROCESSES

2519833 PROCESS

(PROCESS OR PROCESSES)

L17 2427 L16 AND PROCESS

=> s 117 and peroxide or halogen

159105 PEROXIDE

37803 PEROXIDES

174663 PEROXIDE

(PEROXIDE OR PEROXIDES)

92775 HALOGEN

17591 HALOGENS

102322 HALOGEN

(HALOGEN OR HALOGENS)

L18 102346 L17 AND PEROXIDE OR HALOGEN

```
=> s 117 and (peroxide or halogen)
        159105 PEROXIDE
         37803 PEROXIDES
        174663 PEROXIDE
                 (PEROXIDE OR PEROXIDES)
         92775 HALOGEN
         17591 HALOGENS
        102322 HALOGEN
                 (HALOGEN OR HALOGENS)
L19
            72 L17 AND (PEROXIDE OR HALOGEN)
=> s 119 and benzyl trichloromethyl sulfide
        120082 BENZYL
            43 BENZYLS
        120096 BENZYL
                 (BENZYL OR BENZYLS)
          5762 TRICHLOROMETHYL
             2 TRICHLOROMETHYLS
          5763 TRICHLOROMETHYL
                 (TRICHLOROMETHYL OR TRICHLOROMETHYLS)
        255284 SULFIDE
         71298 SULFIDES
        284092 SULFIDE
                 (SULFIDE OR SULFIDES)
             1 BENZYL TRICHLOROMETHYL SULFIDE
                 (BENZYL (W) TRICHLOROMETHYL (W) SULFIDE)
L20
             O L19 AND BENZYL TRICHLOROMETHYL SULFIDE
=> s l19 and sulfur
        274389 SULFUR
           434 SULFURS
        274609 SULFUR
                 (SULFUR OR SULFURS)
L21
            12 L19 AND SULFUR
=> d ibib abs hitstr 1-12
```

#### 09961347 Page 39 09/09/2002

L21 ANSWER 1 OF 12 CAPLUS COPYRIGHT 2002 ACS ACCESSION NUMBER: 2002:271049 CAPLUS DOCUMENT NUMBER: 136:298291

DOCUMENT NUMBER: TITLE:

136:298291
Etching with helogen-containing gas mixtures for removal of rhodium and/or iridium films Vaartstra, Brian A. Micron Technology, Inc., USA U.S., 9 pp. CODEN: USXXAM PALENT

INVENTOR(S): PATENT ASSIGNEE(S): SOURCE:

DOCUMENT TYPE: English

FAMILY ACC. NUM. COUNT: 1 PATENT INFORMATION:

PATENT INFORMATION:

PATENT NO. KIND DATE APPLICATION NO. DATE

US 6368518 B1 20020409 US 1999-382506 19990825

AB The Ir, Rh, or Ir-Rh alloy films on metal or semiconductor substrates are removed by etching with gas or plasma contg. halogen (or halide vapor) and preferably an auxiliary gas. The etching gas mixt. typically contains: (a) halogen, halide, and optionally fluorocarbon or chlorocarbon vapors; and (b) the auxiliary gas, typically CO pro NO: and (c) optional O-contg. gas, esp. 02. The process is suitable for pattern etching of the Ir or Rh films precoated with a resist layer. The typical gas mixt. For etching of Ir electrode film contains #2, CO, and Ar.

REFERENCE COUNT: 15 THERE ARE 15 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L21 ANSWER 3 OF 12
ACCESSION NUMBER:
DOCUMENT NUMBER:
TITLE:
INVENTOR(S):

PATENT ASSIGNEE(S):

CAPLUS COPYRIGHT 2002 ACS
2001:214847 CAPLUS
134:256151
Decomposition treatment agent and decomposition method for organic halogen compounds.
Furuta, Takayuki, Murakami, Tatsuuc Aitou, Shigeru, Akatsuka, Yoshimamaşı Takeuchi, Akihiro
Deda Sekkai Seizo K. K., Japan, Chubu Electric Power
Co. Juc.

Jpn. Kokai Tokkyo Koho, 10 pp. CODEN: JKXXAF SOURCE:

DOCUMENT TYPE:

FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO. KIND DATE APPLICATION NO. DATE

JP 2001079344 A2 20010327 JP 1999-262600 19990916

The org. helogen decompn. agents contain magnesium oxide at .gtoreq.50 wt. % or magnesium oxide and calcium oxide at .gtoreq.50 wt. % in which the mol. ratio of Cao/Cao+NgO is .ltoreq.0.67. The granular agents do not melt and form lumpy masses when in contact with org. helogen decompn. at high temp. (800-1400.degree.).

L21 ANSWER 2 OF 12 CAPLUS COPYRIGHT 2002 ACS
ACCESSION NUMBER: 2001:614312 CAPLUS
DOCUMENT NUMBER: 135:161103
Hethod for planarizing polysilicon layer by etching with oxygen- and halogen-based gas mixture
Lin, Chingfu
Taiwan Semiconductor Manufacturing Co., Ltd., Taiwan SOURCE: U.S., 5 pp.
CODEN: USXXAM
DOCUMENT TYPE: Patent

DOCUMENT TYPE: Patent English LANGUAGE: FAMILY ACC. NUM. COUNT: PATENT INFORMATION:

PATENT INFORMATION:

PATENT NO. XIND DATE APPLICATION NO. DATE

US 627774. B1 20010821 US 1999-282052 19990329

PRIORITY APPLN. INFO.:

AB A method for planarizing a polysilicon layer is described. A polysilicon layer is etched with an O-based gas and a halogen-based gas. The O-based gas comprises an N oxide gas. The N oxide gas includes NO, NO2, N2O, or the combination thereof. The halogen-based gas includes NO, or a combination thereof. The fulloworation includes CF4.

CHP3, CH2F2, CH3F, or the like.

REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L21 ANSWER 4 OF 12 CAPLUS COPYRIGHT 2002 ACS ACCESSION NUMBER: 2001:101447 CAPLUS DOCUMENT NUMBER: 134:140485 TITLE: Sidewall polymer forming

134:140485 Sidewall polymer forming gas additives for plasma stching processes in semiconductor device fabrication Williams, Raney: Chinn, Jeffrey: Trevor, Jitske: Lill, Thorsten B.: Nallan, Padmapani: Varga, Tamas: Mace, INVENTOR(S):

Herve
Applied Materials, Inc., USA
PCT Int. Appl., 32 pp.
CODEN: PIXXD2 PATENT ASSIGNEE(S): SOURCE:

DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO. APPLICATION NO. DATE KIND DATE

PATENT NO. KIND DATE APPLICATION NO. DATE

WO 2001009934 A1 20010208 WO 2000-US21456 20000803
W: JP, KR
RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
PT, SE
P1208588 A1 20020529 EP 2000-950996 20000803
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
IE, SI, LT, LV, FI, RO, MK, CY, AL
PRIORITY APPLN. INFO: US 1999-366509 A 19990803
AB A process of reducing crit. dimension (CD) microloading in dense and isolated regions of etched features of Si-contg. material on a substrate uses a plasma of an etchant gas and an additive gas. In one version, the etchant gas comprises halogen species absent F, and the additive gas comprises F species and C species, or H species and C species.

species. REFERENCE COUNT: THERE ARE 11 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT 11

#### 09961347 Page 40 09/09/2002

L21 ANSWER 5 OF 12 CAPLUS COPYRIGHT 2002 ACS
ACCESSION NUMBER: 2000:540835 CAPLUS
DOCUMENT NUMBER: 133:139536
Hethod and apparatus for suppressing greenhouse gases
INVENTOR(5): 5hoji, Yuichi; Unoki, Kazuo; Nagayama, Kenichi
Toshiba Corp., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 8 pp.
CODEN: JOXOAF
DOCUMENT TYPE: Patent
LANGUAGE: 1000 AUGUST 1 Japan
SOURCE: 1000 AUGUST 1 Japan
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION: and apparatus for suppressing greenhouse effect

KIND DATE APPLICATION NO. DATE

PATENT NO. KINO DATE

JP 2000218129

A2 20000808

JP 1999-22284

JP990129

Emission of CO2 gas generated during treatment of usable resources such as fossil fuels, combustible wastes, and the likes in a molten salt furnace is suppressed by utilizing CO2 for synthesis of HeOH or Storing CO2 to be utilized later. Alternatively, greenhouse effect gases, e.g. CH4, NO2, fluorocarbons, SF6, halogen-contg, gases, and their ligs., can be detoxicated by treating them in a molten salt reactor. The app. for suppressing greenhouse effect gases comprises a molten salt reactor into which the greenhouse effect gases comprises a molten salt reactor, and a molten salt electrolytic regenerator for regenerating the salts in the filtered liq. Another app. is also claimed. CO2 is utilized for HeOH synthesis or as pure CO2 in a closed system and greenhouse effect gases besides CO2 are detoxicated and decompd. with a miniaturized app.

L21 ANSWER 6 OF 12 CAPLUS COPYRIGHT 2002 ACS (Continued) acid/base rather than redox chem. and the occurrence of fragmentation at the surface rather than after departure. The silyl ions show ion/surface reactions which are dominated by fluorine abstraction from the surface but they also include such remarkable processes as fluorine-for-Me substitution, which occurs with the isothiocyanate projectile ion (4). Surface modification of fluorinated self-assembled monolayer surfaces was accomplished by prolonged bombardment with low-energy OCNCS+ and (CH3) 2SINCS+ ions. Evidence is provided for incorporation of Me, silyl, and NCS groups into the modified surface, although the energetic conditions needed to cause the bond dissoons. necessary for ion/surface reactions make the formation of modified surfaces esp. difficult in these cases.

L21 ANSWER 6 OF 12 CAPLUS COPYRIGHT 2002 ACS ACCESSION NUMBER: 1997:214996 CAPLUS DOCUMENT NUMBER: 126:334853

126:334853 Ion/surface reactions, surface-induced dissociation and surface modification resulting from hyperthermal collisions of OCNCO+, OCNCS+, (CR3) 251NCO+, and (CH3) 251NCS+ with a fluorinated self-assembled

(CH3)2SiNCS+ with a fluorinated self-assembled monolayer surface miller, S. A.; Luo, H.; Jiang, X.; Rohrs, H. W.; Cooks, R. G.
Department of Chemistry, Purdue University, West Lafayette, USA
International Journal of Mass Spectrometry and Ion Processes (1997), 160 (1-3), 83-105
CODEN: IJMPDN, ISSN: 0168-1176

CORPORATE SOURCE:

SOURCE:

PUBLISHER: Elsevier DOCUMENT TYPE: LANGUAGE:

AUTHOR(S):

Processes (1997), 160(1-3), 83-105

CODEN: IJMPON, ISSN: 0168-1176

LISHER: Elsevier

LIMENT TYPE: Journal

BUAGE: English

Low-energy (10-90 eV) collisions of the pseudohalogen-contg. ions OCNCO+

(1), OCNCS+ (2), (CM3) ZSINCO+ (3), and (CM3) ZSINCS+(4) with fluorinated

self-assembled (F-SNM) monolayer surfaces lead to surface-induced dissocn.

(SID) and to a variety of ion/surface reactions. The lowest energy
fragmentation process in both OC-NCO+ and OC-NCS+ is C-N bond

cleavage but the strength of these bonds is significantly different. They

are estd. from surface-induced dissocn. data taken as a function of

collision energy (energy resolved mass spectra) to be 4 and 3 eV, resp.

The silyl ions, (3) and (4), preferentially fragment by Si-C bond cleavage

and charge retention by the suffur in preference to oxygen is

and charge retention by the suffur in preference to oxygen is

evident in the isothiocyanate spectra. The collision energy dependence of

the scattered ion spectra display the competition between elastic

scattering, dissocn., reaction, and surface sputtering. The extent of

sputtering increases with collision energy and is greater in (1) and (2)

than it is in the silicon-contg. ions (3) and (4), and the implications of

this result for the ionization energy of the radicals corresponding to

(1)-(4), are addressed. On the other hand, OCNCO+ and OCNCS+ are less

reactive than their silyl counterparts, and data suggest that the obad.

reactions do not proceed by charge exchange but instead by a direct

reaction mechanism. The reaction products in the two pairs of ions (e.g.

FOO- from (1), FCS+ from (2), vs. SiP+ and SiNZP+ from (3) and (4)) are

notably different, consistent with the differences in the SID behavior and

showing that the major reactive site in (3) and (4) is the silicon atom.

Comparisons between the isocyanates and isothiocyanates show that the NCS

group confers much greater reactivity than the NCO group within each pair

of projectile ions. Analogies are found in the OCNCO+

L21 ANSWER 7 OF 12 CAPLUS COPYRIGHT 2002 ACS
ACCESSION NUMBER: 1995:316220 CAPLUS
DOCUMENT NUMBER: 123:45714
ITITLE: 123:45714
Dry etching of silicon compound layers
Yanaqida, Toshiharu
Sony Corp., Japan
U.S., 8 pp.
DOCUMENT TYPE: USXXAM
DOCUMENT TYPE: English
FAMHLY ACC. NUM. COUNT: 1

DOCUMENT TYPE: LANGUAGE: FAMILY ACC. NUM. COUNT: PATENT INFORMATION:

PATENT NO. KIND DATE APPLICATION NO. DATE

US \$376234 A 19941227 US 1993-78928 19930621

JP 3109253 B2 2001113 JP 1992-170980 19920629

PRIORITY APPLN. INFO::

B2 2001113 JP 1992-170980 19920629

B3 A mercaptan, a thicether, and/or a disulfide having a fluorocarbon side chain is used as a main component of the etching gas. These compds. may form CFr4 and S on dissocn. due to elec. discharges, and contribute to high-rate etching and surface protection of a wafer. If a halogen compd. such as COFZ, SOFZ, or NOF is added to the etching gas, a high-rate etching reaction due to extn. of 0 atoms from \$102\$ and structured reinforcement of carbonaceous polymer become possible. Also, \$2FZ may be added for reinforcing deposition of S. These effects lead to a redn. of the amt. of deposited polymer necessary for highly selective processing, and contribute greatly to low pollution in a process.

#### 09961347 Page 41 09/09/2002

L21 ANSWER 8 OF 12 CAPLUS COPYRIGHT 2002 ACS

ACCESSION NUMBER: 1994:686783 CAPLUS

121:226783

LOW-Energy Collisions of Group IIIA, IVA, VA, VIA, and VIIA Ions with fluoroalkyl SAM Surfaces: Reactions, Chemical Sputtering, and Mechanistic Implications

AUTHOR(S): Pradeep, T.; Ast, T.; Cooks, R. G.; Feng, B.

Department of Chemistry, Purdue University, Vest

Lafayette, IN, 4797, USA

SOURCE: J. Phys. Chem. (1994), 98 (37), 9301-11

COOEM: DPCHAX; ISSN: 0022-3654

DOCUMENT TYPE: Journal

LANGUAGE: English

Lafayette, IN, 47907, USA

J. Phys. Chem. (1994), 98(37), 9301-11

CODEN: JPCHAX; ISSN: 0022-3654

DOCUMENT TYPE: Journal

LANGUAGE: English

AB Low-energy (10-90 eV) at. ions of Group IIIA, IVA, VA, VIA, and VIIA

elements (E) undergo reactions with a fluorinated self-assembled monolayer

surface to give fluoride cations, EFn; 1, 2, or 3 F atoms can be

abstracted. Ion/surface reactions are also obsd. with polyat. ions of

these elements, but in general, at. ions are much more reactive and react

at lower collision energies reflect increased energy consumption needed for

fragmentation. Most of the ion/surface reactions studied in this study

are endothermic and are driven by the translational energy of the

projectile, although there remains a high degree of thermochem. control

over reactivity. Thermochem. control over neutralization of the primary

beam is also evident; ions with high recombination energies (e.g., N+ and

O+) completely neutralize at the fluorocarbon surface. In

addn., certain general trends in behavior are obsd. for elements within

the same periodic group. The reactions occur in single scattering events,

and they are not assocd, with electron transfer from the ion to the

surface, as are the well-known H and alkyl group abstractions by org.

radical ions. The surface has no memory of the projectile, even after

prolonged ion beam exposure. In most cases, the ion/surface reaction

seems to occur after, or in concert with, dissocn, of the polyat.

projectile. When multiple abstractions occur the F atoms can be lost

from the same alkyl chain; evidence for this is the enhanced intensity of

specific sputtering products (e.g., C373+) upon collisions of ions (e.g.,

Sb+) which readily abstr. > 1 F atom, Ion/surface reactions in which new

bonds are formed in the surface alkyl group are also obsd.; such reactions

broduce unusual product ions which are sensitive to the cheen, nature of

the projectile. Examples include C1-for-F atom substitution at the

surface and PCF2+ formation in Pr colli

ACCESSION NUMBER: DOCUMENT NUMBER: TITLE:

ANSWER 10 OF 12 CAPLUS COPYRIGHT 2002 ACS
SSSION NUMBER: 1991:582630 CAPLUS

LE: 1991:582630 CAPLUS
Pluerocarbon compounds and processes
for preparation thereof
Krespan, Carl George
du Pont de Nemours, E. I., and Co., USA
CE: CT Int. Appl., 26 pp.
CODEN: PIXXD2
MENT TYPE: Patent INVENTOR(S): PATENT ASSIGNEE(S): SOURCE:

DOCUMENT TYPE: LANGUAGE: FAMILY ACC. NUM. COUNT: PATENT INFORMATION:

PATENT NO.	KIND	DATE			
WO 9109010				WO 1990-US711	4 19901210
WO 9109010	A3	19910905			
W: CA, JP					
RW: AT, BE,	CH, DE	, DK, ES,	FR, G	B, GR, IT, LU,	NL, SE
US 5101058	À	19920331		US 1989-44865	1 19891211
CA 2071199	AA	19910612		CA 1990-207115	99 19901210
EP 504285	A1	19920923		EP 1991-901382	2 19901210
EP 504285					
R: DE, FR,					
JP 05502866	T2	19930520		JP 1991-50176	7 19901210
JP 3172173				** ****	
JP 2000053665				TR 1000-201501	19901210
US 5185477					
JP 2000053604				JP 1999-20148	5 19990/15
JP 3130303	В2	20010131			
PRIORITY APPLN. INFO	. :		US	1989-448651	A 19891211
			JP	1991-501767	A3 19901210
				1990-US7114	
OTHER SOURCE(S):	W.	RPAT 115:			
	na	MENT III	102030		
GI					

OTHER SOURCE(S):

R2R3FC CFR2R3

Fluorinated (poly) sulfonates and halosulfonates R2R3FCCHXCHR1(OSO2) nZ (R1 = H, CFR2R3; R2, R3 = F, perfluoroalkyl; R1 = H, CFR2R3; X = C1, Br, iodor Z = C1, Br, OCRRICHXCFR2R3; n = 1-6), halohydrins R2R3CHXCH(OH)CFR2R3, and epoxides (1), useful as monomers and chem: intermediates, are prepd. by reacting (perfluoroalkyl) ethylenes R2R3FCCH:CHR1 with SO3 and a halogen, i.e. C1, Br or iodine; in the optional presence of a solvent, and further reacting the products. Thus, 0.13 mol CF3(CF2)3CH:CH2 was added to 0.12 mol SO3 with sticring at 25.degree. followed by 0.12 mol 1, whereupon an exotherm carried to 45.degree. and then abated. The mixt. was stirred overnight at 25.degree, and then abated. The mixt. was stirred overnight at 25.degree. and then at 50.degree. for 30 min, evapd. in vacuo at 0.15 mmHg, stirred with H2O, filtered and air-dried to give 58% (based on SO3) [CF3(CF2)3CHICH2O]2SO2.

L21 ANSWER 9 OF 12 CAPLUS COPYRIGHT 2002 ACS
ACCESSION NUMBER: 1994:522988 CAPLUS
DOCUMENT NUMBER: 121:122988
17IILE: 17IILE:

and Sro Kobayashi, Hidehiko; Kusunoki, Hideki; Ishikawa, Itsuo; Nagaseki, Kazuya; Saito, Yukinori; Suganomata, AUTHOR (S):

Shinji Fac. Samanashi Univ., Kofu, 400, Japan Shinku (1994), 37(3), 308-11 CODEN: SHINAM; ISSN: 0559-8516 Journal CORPORATE SOURCE: SOURCE:

DOCUMENT TYPE:

LANGUAGE:

AB The electronegativities and discharge characteristics of helogen

-contg, gases such as CF4 and SF6 are compared. These gases are

discharged between parallel plate electrodes and used for etching

process for semiconductor device fabrication.

L21 ANSWER 11 OF 12 CAPLUS COPYRIGHT 2002 ACS
ACCESSION NUMBER: 1984:478619 CAPLUS
DOCUMENT NUMBER: 101:78619
On the scavenging of sulfur dioxide by cloud
and raindrops: II. An experimental study of
sulfur dioxide absorption and desorption for
water drops in alr
Walcek, C. J.; Pruppacher, H. R.; Topalian, J. H.;
Mitra, S. K.

CORPORATE SOURCE: Dep. Atmospheric Sci., Univ. California, Los Angeles,
CA, 90024, USA
J. Atmospheric Sci., Univ. California, Los Angeles,
CA, 90024, USA
J. Atmospheric Sci., Univ. California, Los Angeles,
COEN: JATCE2
JOURNAT TYPE: LANGUAGE: English
AB For the purpose of testing our previously described theory of SO2
scavenging, a lab. investigation was carried out in the UCLA 33 m long
rainshaft. Drops with radii between 250 and 250. mu.m were allowed to
come to terminal velocity, after which they passed through a chamber of
variable length filled with various SO2 concens. in air. After falling
through a gas seps. chamber consisting of a fluoroccarbon gas,
the drops were collected and analyzed for their total S content to det.
the rate of SO2 absorption. The SO2 concn. in air was 1-60 vol.1. Such
relatively large concns. were necessary due to the short times the drops
were exposed to SO2. Theor. S concn. in the drops agreed well with those
obsd., if the drops had radii <500 .mu.m. To obtain agreement between
predicted and obsd. S concns. in the drops agreed well with those
obsd., if the drops had radii <500 .mu.m. To obtain agreement between
to fall through s-free air to det. the rate of SO2 desorption. The
results agreed well with the results of the theor. model, thus justifying
the reversibility assumption. The effects of oxidn. on SO2 absorption was
studied by means of drops contg. various amts. of H2O2. For comparable
exposure times to SO2, the Sconcn. in drops with H2O2 was 10 times higher
than the concn. in drops in which no oxidn. occurred.

## 09961347 Page 42 09/09/2002

L21 ANSWER 12 OF 12 CAPLUS COPYRIGHT 2002 ACS
ACCESSION NUMBER: 1983:514428 CAPLUS
DOCUMENT NUMBER: 99:114428
TITLE: Silicon surface treatment in halogen
-containing plasma
AUTHOR(S): Dikarev, Yu. I., Esin, V. I., Naumenko, N. I.
Voronezh, USSR
Fiz. Khim. Obrab. Mater. (1983), (4), 61-5
CODEN: FKOMAT; ISSN: 0015-3214
DOCUMENT TYPE: Journal
LANGUAGE: Russian
AB The processes of etching were studied of single-crystal Si with
different orientations and surface treatments in the plasma of a
high-frequency discharge of F-conto, gases at pressures of 13.3-133.3 Pa.
By changing the tech. parameters of the process, one can obtain
both pure etching of Si and deposition of films identified as
fluorocarbon. During plasmachem. etching of a polished surface,
only insignificant smoothing of the initial relief occurs with development
of an etching figure characteristic for the given orientation.
Electronog, studies of samples after plasmachem. etching in the polishing
regime show the absence of amorphization of the surface in the treatment
process.

=> s fluorocarbon/p
'p' IS NOT A VALID FIELD CODE
L23 0 FLUOROCARBON/P

=> fil caplus
COST IN U.S. DOLLARS

SINCE FILE TOTAL
ENTRY SESSION
FULL ESTIMATED COST

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09961347 Page 44 09/09/2002

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STRUCTURE FILE UPDATES: 6 SEP 2002 HIGHEST RN 447682-31-7 DICTIONARY FILE UPDATES: 6 SEP 2002 HIGHEST RN 447682-31-7

TSCA INFORMATION NOW CURRENT THROUGH MAY 20, 2002

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Crossover limits have been increased. See HELP CROSSOVER for details.

Calculated physical property data is now available. See HELP PROPERTIES for more information. See STNote 27, Searching Properties in the CAS Registry File, for complete details: http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf

=>
Uploading 09961347b.str

L24 STRUCTURE UPLOADED

=> d L24 HAS NO ANSWERS L24 STF



G1 O, S, Po, Se, Te

Structure attributes must be viewed using STN Express query preparation.

=> s 124

SAMPLE SEARCH INITIATED 11:59:11 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 5036 TO ITERATE

19.9% PROCESSED 1000 ITERATIONS INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED) SEARCH TIME: 00.00.01

50 ANSWERS

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*

BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS: 96468 TO 104972 PROJECTED ANSWERS: 94495 TO 102915

L25 50 SEA SSS SAM L24

=> s 124 full FULL SEARCH INITIATED 11:59:17 FILE 'REGISTRY' FULL SCREEN SEARCH COMPLETED - 100762 TO ITERATE

97689 ANSWERS 100.0% PROCESSED 100762 ITERATIONS

SEARCH TIME: 00.00.04

L26 97689 SEA SSS FUL L24

=> fil caplus COST IN U.S. DOLLARS SINCE FILE

TOTAL SESSION ENTRY 140.28 651.32 FULL ESTIMATED COST

TOTAL

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS) SINCE FILE TOTAL

ENTRY SESSION 0.00 -7.43 CA SUBSCRIBER PRICE

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FILE COVERS 1907 - 9 Sep 2002 VOL 137 ISS 11 FILE LAST UPDATED: 8 Sep 2002 (20020908/ED)

This file contains CAS Registry Numbers for easy and accurate substance identification.

CAS roles have been modified effective December 16, 2001. Please check your SDI profiles to see if they need to be revised. For information on CAS roles, enter HELP ROLES at an arrow prompt or use the CAS Roles thesaurus (/RL field) in this file.

=> s 126

L27 50443 L26

=> s 127 and (peroxide or halogen)

159105 PEROXIDE

37803 PEROXIDES

174663 PEROXIDE

(PEROXIDE OR PEROXIDES)

92775 HALOGEN

17591 HALOGENS

102322 HALOGEN

(HALOGEN OR HALOGENS)

2065 L27 AND (PEROXIDE OR HALOGEN) L28

=> s 128 and fluorocarbon

12055 FLUOROCARBON

. 3750 FLUOROCARBONS 13705 FLUOROCARBON

(FLUOROCARBON OR FLUOROCARBONS)

L29 16 L28 AND FLUOROCARBON

=> d ibib abs hitstr 1-16

```
L29 ANSWER 2 OF 16 CAPLUS COPYRIGHT 2002 ACS
ACCESSION NUMBER: 1999:534597 CAPLUS
DOCUMENT NUMBER: 131:336721
TITLE: The reaction of difluorodioxirane with cesium
trifluoromethoxide
thang Qun; DemMarteau, Darryl D.
CORPORATE SOURCE: Department of Chemistry, Clemson University, Clemson, SC, USA
SOURCE: Chemical Communications (Cambridge) (1999), (17),
1671-1672
CODEN: CHCOFS, ISSN: 1359-7345
PUBLISHER: Royal Society of Chemistry
DOCUMENT TYPE: Journal
LANGUAGE: English
OTHER SOURCE(S): CASREACT 131:336721
AB The reaction of difluorodioxirane with cesium trifluoromethoxide in the presence of CsF forms CF300C(o)F and the new compds. CF30(0CF20) nOC(o)F (n - 1 3): 13C labeling shows that the dioxirane undergoes ring opening at the 0-0 bond.

13 i6118-40-49 249729-77-99 249729-78-09
249729-80-4P
RL: SPN (Synthetic preparation); PREP (Preparation)
(reaction of difluorodioxirane with carbonyl difluoride in presence of cesium fluoride)
RN 16118-40-4 CAPLUS
CN Carbonofluoridoperoxoic acid, trifluoromethyl ester (9CI) (CA INDEX NAME)

O
F-C-O-O-CF3
RN 249729-78-0 CAPLUS
CN Carbonofluoridoperoxoic acid, [[difluoro[(trifluoromethyl)dioxy]methyl]dioxy]difluoromethyl ester (9CI) (CA INDEX NAME)

O
F-C-O-O-CF2-O-O-CF2-O-O-CF3
RN 249729-78-0 CAPLUS
CN Carbonofluoridoperoxoic acid, [[difluoro[(trifluoromethyl)dioxy]methyl]dioxy]difluoromethyl ester (9CI) (CA INDEX NAME)

O
F-C-O-O-CF2-O-O-CF2-O-O-CF3
RN 249729-80-4 CAPLUS
CN Carbonofluoridoperoxoic acid, [[[difluoro[(trifluoromethyl)dioxy]methyl]dioxy]difluoromethyl]dioxy]difluoromethyl ester (9CI) (CA INDEX NAME)
```

```
L29 ANSWER 1 OF 16 CAPLUS COPYRIGHT 2002 ACS (Continued)
L29 ANSWER 2 OF 16 CAPLUS COPYRIGHT 2002 ACS (Continued)
F-C-0-0-CF2-0-0-CF2-0-0-CF2-0-0-CF3
                           10 THERE ARE 10 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT
REFERENCE COUNT:
```

### 09961347 Page 48 09/09/2002

```
L29 ANSWER 3 OF 16 CAPLUS COPYRIGHT 2002 ACS ACCESSION NUMBER: 1997:286376 CAPLUS DOCUMENT NUMBER: 126:264472
                                                                                                                             126:264472
Manufacture of acyl peroxides
Diffendall, George Francis; Harding, Thomas William;
Hockman, Joseph Norman; Targett, Hatthew John;
Wheland, Robert Clayton; Krespan, Carl George
E.1. Du Pont De Nemours and Company, USA
PCT Int. Appl., 56 pp.
CODEN: PIXXO2
Patent
PROBLES
     INVENTOR(S):
     PATENT ASSIGNEE(S):
SOURCE:
     DOCUMENT TYPE:
LANGUAGE:
   LANGUAGE: English FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:
                          PATENT NO. KII
                                                                                                                                                                                                                         APPLICATION NO. DATE
                                                                                                               KIND DATE
                          W0 9708142 A1 19970306 W0 1996-US13976 19960830

W: CA, JP

RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE

US 5831131 A 19981103 US 1996-703232 19960826

CA 230606 AA 19970306 CA 1996-2230606 19960830

EP 847387 A1 19980617 EP 1996-931442 19960830

EP 847387 B1 20020102

R: DE
                                                                                                           A1 19970306
                                                                                                                                                                                                                         WO 1996-US13976 19960830
                      TI INC.

JP 11511464 T2 1991005 JF 1996-510595 19960830
US 5962746 A 19991005 US 1998-128506 19980804

PRITY APPLN. INFO.: US 1995-2961P P 19950830
US 1996-703232 A 19960826
US 1996-703232 A 19960826

A process for the faster manufg. of hydrocarbon, fluorocarbon and chlorocarbon acyl peroxides, useful as polymn. initiators and in org. synthesis, is disclosed wherein a metal or tetraalkylammonium hydroxide, a peroxide and an acyl halide are reacted under continuous vigorous agitation conditions so as to bring the reaction to substantial completion in less than one minute.

90275-06-29
RI: CAT (Catalvst use): IMP // CATAL CA
 ur 11511464 T2 19991005
US 5962746 A 19991005
PRIORITY APPLN. INFO.:
                        90275-06-2P

RL: CAT (Catalyst use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)

(manuf. of acyl peroxides for polymn. catalysts by reaction of acyl halides, hydroxides, peroxides under vigorous agitation)
90275-06-2 CAPLUS
Peroxide, bis[2,3,3,3-tetrafluoro-1-oxo-2-(trifluoromethoxy)propyl] (9CI) (CA INDEX NAME)
                        2927-83-5
RL: RCT (Reactant); RACT (Reactant or reagent)
 L29 ANSWER 4 OF 16 CAPLUS COPYRIGHT 2002 ACS
ACCESSION NUMBER: 1996:71567 CAPLUS
DOCUMENT NUMBER: 124:178666
Fluorocarbon rubbers modified by silicone resins
INVENTOR(5): Gentle, Thomas M.; Gornowicz, Gerald A.
DOCUMENT TYPE: DOCUMENT TYPE: CODEN: USXXAM
DOCUMENT TYPE: PAMILY ACC. NUM. COUNT: PATENT INFORMATION:
vk.
56357-87-0. Tetrafluoroethylene-trifluoromethyl trifluorovinyl
ether-vinylidene fluoride copolymer
RL: POF (Polymer in formulation), PRP (Properties), TEM (Technical or
engineered material use), USES (Uses)
(rubber; silowane resin-contg. fluororubber compns. with low fuel
permeability and good cold resistance)
56357-87-0 CAPLUS
Ethene, tetrafluoro-, polymer with 1,1-difluoroethene and
trifluoro(trifluoromethoxy)ethene (9CI) (CA INDEX NAME)
                           CH 1
                          CRN 1187-93-5
CMF C3 F6 O
 CF2
||
F-C-O-CF3
```

Examiner Anderson 703-605-1157

CM 2 CRN 116-14-3 CMF C2 F4

#### 09961347 Page 49 09/09/2002

```
L29 ANSWER 5 OF 16 CAPLUS COPYRIGHT 2002 ACS
ACCESSION NUMBER: 1995:362702 CAPLUS
DOCUMENT NUMBER: 122:239348
Cyclofluoroalkylated fc
INVENTOR(5): Bekiarian, Paul G., Fag
du Pont de Nemours, E.
SOURCE: U.S., 6 pp.
                                                                                                                                                                 PLUS COPYRIGHT 2002 ACS
1995:362702 CAPLUS
122:239348
Cyclofluoroalkylated fullerene compounds
Bekiarian, Paul G.; Fagan, Paul J.; Krusi
du Pont de Nemours, E. I., and Co., USA
U.S., 6 pp.
CODEN: USXXAM
Patent
English
1
                                                                                                                                                                                                                                                                                                                                                                                                                                      usic, Paul J.
      DOCUMENT TYPE:
LANGUAGE:
FAMILY ACC. NUM. COUNT:
PATENT INFORMATION:
                                     PATENT NO.
                                                                                                                                                     KIND DATE
                                                                                                                                                                                                                                                                                             APPLICATION NO. DATE
PATENT NO. KIND DATE APPLICATION NO. DATE

US 5382718 A 19950117 US 1993-122118 19930916
US 5416243 A 19950516 US 1994-297334 19940829
WO 9507875 A1 19950323 WO 1994-US10103 19940915
W: CA, JP
RW: AT, BE, CH, DE, DN, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE
PRIORITY APPLN. INFO: US 1993-122118 19930916
OTHER SOURCE(S): MARRAT 122:239348
AB Mixts. of cyclofluoroalkylated fullerenes are provided by the thermal [2 + 2] cycloaddn. of fluoroalkenes to a soln. or slurry of a fullerene. The cyclofluoroalkylated fullerene mixts. are useful as lubricants or additives to lubricants; in fluorocarbon and/or chlorofluorocarbon based cooling systems; in adhesives for fluorocarbon based cooling systems; in adhesives for fluorocarbon based cooling systems; in adhesives for fluorocarbon based polymers and in gas sepn. membranes (no data).

IT 187-93-5DP, Perfluoro(methyl vinyl sther), reaction products with fullerene
RL: SFN (Synthetic preparation); PREP (Preparation)
(preph. of cyclofluoroalkylated fullerene mixts. via thermal [2+2] cycloaddn. reaction of fullerenes with fluoroalkenes)
RN 187-93-5 CALUS
CN Ethene, trifluoro(trifluoromethoxy)- (9CI) (CA INDEX NAME)
```

CF2 || |F-C-O-CF3

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L29 ANSWER 7 OF 16 CAPLUS COPYRIGHT 2002 ACS ACCESSION NUMBER: 1992:513758 CAPLUS DOCUMENT NUMBER: 117:113758 CAPLUS SOLID materials and access to the company of the compa
                                                                                                                                                                                                              117:113758
Solid materials with reduced surface energy and surface treatment for obtaining the same Tadenuma, Katsuyoshi: Kawamura, Fumiaki
  INVENTOR(S):
PATENT ASSIGNEE(S):
SOURCE:
                                                                                                                                                                                                              Japan
Jpn. Kokai Tokkyo Koho, 14 pp.
CODEN: JXXXAF
    DOCUMENT TYPE:
                                                                                                                                                                                                                Patent
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:
                                      PATENT NO. Kinu ....

JP 04048075 A2 19920218
B2 19991206
B2 19991206
                                                                                                                                                                                                                                                                                                                                                             APPLICATION NO. DATE
                                                                                                                                                                                                                                                                                                                                                             JP 1990-158500 19900615
                                  JP 04048075 A2 19920218 JP 1990-1585500 19900615
JP 2986513 B2 19991206
The title materials have fluorocarbon groups chem. bonded on the surface. Treatment of glass and ceramics with Freon 12 and Freon 13 with .gamma.-ray or microwave irradn. was esp. effective for reduced surface energy (increased water contact angle).

927-04-4, Bis(trifluoromethyl) peroxide
RL: USES (Uses)
[solids surface energy redn. by surface treatment with)
927-84-4 CAPLUS
Peroxide, bis(trifluoromethyl) (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)
ΙŢ
```

F3C-0-0-CF3

```
L29 ANSWER 6 OF 16 CAPLUS COPYRIGHT 2002 ACS ACCESSION NUMBER: 1995: 316220 CAPLUS DOCUMENT NUMBER: 123:45714
                                                                                            Dry etching of silicon compound layers
Yanagida, Toshiharu
   TITLE:
INVENTOR(S):
  PATENT ASSIGNEE(S):
SOURCE:
                                                                                            Sony Corp., Japan
U.S., 8 pp.
CODEN: USXXAM
  DOCUMENT TYPE:
                                                                                             Patent
                                                                                             English
   LANGUAGE:
  FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:
                                                                                                                                                              APPLICATION NO. DATE
US 576234 A 19941227 US 1993-78928 19930621

JP 3109253 B2 20001113 JP 1992-170980 A 19920629

PRIORITY APPLN. INFO.:

AB A mercaptan, a thioether, and/or a disulfide having a fluorecambon side chain is used as a main component of the etching gas. These compds. may form CFM+ and S on dissocn. due to elec. discharges, and contribute to high-rate etching and surface protection of a wafer. If a halogen compd. such as COF2, SOF2, or NOF is added to the etching gas, a high-rate etching reaction due to extn. of O atoms from SiO2 and structural reinforcement of carbonaceous polymer become possible. Also, SZF2 may be added for reinforcing deposition of S. These effects lead to a redn. of the amt. of deposited polymer necessary for highly selective processing, and contribute greatly to low pollution in a process.

IT 372-64-5, Bis(trifluoromethyl) disulfide
RI: PEP (Physical, engineering or chemical process), PROC (Process)
(plasma etching of silicon compd. layers in gas mixts. Contg.)
                     PATENT NO.
                                                                                 KIND DATE
                    Disulfide, bis(trifluoromethyl) (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)
```

F3C-S-S-CF3

```
L29 ANSWER 8 OF 16 CAPLUS COPYRIGHT 2002 ACS
ACCESSION NUMBER: 1991:582630 CAPLUS
DOCUMENT NUMBER: 115:182630
TITLE: preparation thereof
INVENTOR(5): Krespan, Carl George
ATENT ASSIGNEE(S): du Pont de Nemours, E. I., and Co., USA
SOURCE: CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
 LANGUAGE:
FAMILY ACC. NUM. COUNT:
PATENT INFORMATION:
             PATENT NO. KIND DATE

WO 9109010 A2 19910627 WO 1990---
WO 9109010 A3 19910905

W: CA, JP
RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LU, NL, SE
US 5101059 A 19920331 US 1989-448651 19891211
CA 2071199 AA 19910612 CA 1990-2071199 19901210
EP 504285 A1 19920923 EP 1991-901382 19901210
EP 504285 B1 19941012
R: DE, FR, GB, IT
JP 05502866 T2 19930520 JP 1991-501767 19901210
JP 3172173 B2 20010604
JP 2000053665 A2 20000222 JP 1999-201502 19901210

"77 A 19930209 US 1991-803441 19911204
"77 A 19930209 US 1991-803441 19911204
"77 A 19930209 JP 1999-201485 19990711
"78 1989-448651 A 1989121
"79 1999-201485 19990711"
"79 1999-201485 19990712"
"79 1999-201485 19990712"
"79 1999-201485 19990712"
"79 1999-201485 19990712"
"79 1999-201485 19990712"
JP 05502966
JP 3172173
JP 2000053665
US 5185477
JP 2000053604
JP 3130303
PRIORITY APPLN. INFO.:
                                                                                                                                      US 1989-448651 A 3 19991210
UP 1991-501767 A 3 19901210
WO 1990-US7114 W 19901210
MARPAT 115:182630
 OTHER SOURCE(S):
```

```
R<sup>2</sup>R<sup>3</sup>FC
                        CFR2R3
```

AB Fluorinated (poly)sulfonates and halosulfonates R2R3FCCHXCHR1 (0502)nZ (R1 = H, CFR2R3; R2, R3 = F, perfluoroalkyl; R1 = H, CFR2R3; X = C1, Br, iodo; Z = C1, Br, ockR1CkXCFR2R3; n = 1-6), halohydrins R2R3CHXCH(OH)CFR2R3, and epoxides (I), useful as monomers and chem. intermediates, are prepd. by reacting (perfluoroalkyl)ethylenes R2R3FCCH:CHR1 with 503 and a halogam, i.e. C1, Br or iodine, in the optional presence of a solvent, and further reacting the products. Thus, 0.13 mol CF3(CF2)3CH:CHZ was added to 0.12 mol 503 with stirring at 25.degree. followed by 0.12 mol 1, whereupon an exotherm carried to 45.degree. and then abated. The hairt, was stirred overnight at 25.degree, and then at 50.degree. for 30 min, evept in vacuo at 0.15 mmHg, stirred with H2O, filtered and air-dried to give 58% (based on S03) (CF3(CF2)3CHICH2O]2502. RT 1493-13-6, Trifluoromethaneoulfonic acid
RI RCT (Reactant)
(addn. reaction of, with bis(perfluorobutyl)ethylene oxide)

## 09961347 Page 50 09/09/2002

ANSWER 8 OF 16 CAPLUS COPYRIGHT 2002 ACS (Continued)
Methanesulfonic acid, trifluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)

S5:176764
Direct synthesis of fluorocarbon
peroxides. II. The addition of
fluoroperoxytrifluoromethane to alkenes
Rhohorst, Frederick A.; Desmarteau, Darryl D.
Dep. Chem., Kansas State Univ., Manhattan, Kans., USA
Inorg, Nucl. Chem. - Herbert H. Hyman Hem. Vol. (1976)
, 63-6. Editor(s): Katz, Joseph J.; Sheft, Irving.
CODEN: 33TZAU
CODEN: 33TZAU
Conference CORPORATE SOURCE: Conference
Figure English
F3COOF reacted with alkenes, C2H4, C2F3Cl, perfluoropropene, and
perfluorocyclopentens, to give the expected peroxides which were
characterized by it and NHR. Thus, treatment of C2F3Cl gave F3COCF2CF2Cl,
F3COCFC1CF3, F3COOCFC1CF3, and F3COOCF2CF2Cl.
1561-50-89 84362-31-1P 59426-77-69
60301-71-89 60301-73-69 60301-73-78
60301-77-18 60301-73-99 60301-73-79
60301-77-18
KL: SPN (Synthetic process.) DOCUMENT TYPE: RL: SPN (Synthetic preparation); PREP (Preparation) (prepn. of) 1561-50-8 CAPLUS Ethane, 1-chloro-1,1,2,2-tetrafluoro-2-(trifluoromethoxy)- (9CI) (CA INDEX NAME) F3C-0-CF2-CF2-C1

L29 ANSWER 10 OF 16 CAPLUS COPYRIGHT 2002 ACS ACCESSION NUMBER: 1976:576764 CAPLUS DOCUMENT NUMBER: 85:176764 TITLE: Direct synthesis of fluo

54362-31-1 CAPLUS Peroxide, 2-chloro-1,1,2,2-tetrafluoroethyl trifluoromethyl (9CI) (CA INDEX NAME)

F3C-0-0-CF2-CF2-C1

59426-77-6 CAPLUS Propane, 1,1,1,2,2,3,3-heptsfluoro-3-(trifluoromethoxy)- (9CI) (CA INDEX NAME)

F3C-0-CF2-CF2-CF3

60901-71-5 CAPLUS Ethane, 1-chloro-1,2,2,2-tetrafluoro-1-(trifluoromethoxy)- (9CI) (CA INDEX NAME)

Examiner Anderson 703-605-1157

L29 ANSWER 9 OF 16 CAPLUS COPYRIGHT 2002 ACS
ACCESSION NUMBER: 1980:638741 CAPLUS
DOCUMENT NUMBER: 93:238741
TITLE: 93:238741
AUTHOR(S): Shack, Carl J., Christe, K. O.
CORPONATE SOURCE: Rockedyne, Div. Rockwell Int., Canoga Park, CA, 91304, USA
SOURCE: J. Fluorine Chem. (1980), 16(1), 63-73
CODEN: JFLCAR; ISSN: 0022-1139
DOCUMENT TYPE: Journal
LANGUAGE: Regist
AB The reaction of simple fluorocarbon halides with CloSo2F or its mixts. with BrOSO2F to produce RfOSO2F (Rf = perfluoroalkyl) has been investigated. In many cases even primary chlorine in CF2X are more readily replaced. The mechanism of this replacement reaction has been established by the isolation of the metastable intermediate RfI (OSO2F)2. Neither secondary chlorine nor bromine in CFX groups is affected. With the secondary indice (CF3)2CFI, the salt [[(CF3)2CF]2I]+ [I(OSO2F)4-] is formed. Furthermore, CloSO2F is capable of converting fluorocarbon acids or their derivs. into fluorocarbon halides. A combination of these two CloSo2F reactions with the known conversion of RfCFZOSO2F to the corresponding fluorocarbon acid offers a novel, high yield chain shortening reaction.

IT 6059-31-49
RL: SPN (Synthetic preparation), PREP (Preparation)
(prepn. of, by reaction of halones fluorocarbon (prepn. of, by reaction of halones fluorocarbon)
(prepn. of, by reaction of halones fluorocarbon) RE: SPN (Synthetic preparation); PREP (Preparation) (prepn. of, by reaction of halogen fluorosulfate with fluorinated carboxylic acid) 6069-31-4 CAPLUS

Fluorosulfuric acid, chlorodifluoromethyl ester (8CI, 9CI) (CA INDEX

L29 ANSWER 10 OF 16 CAPLUS COPYRIGHT 2002 ACS (Continued)
RN 60901-72-6 CAPLUS
CN Peroxide, 1-chloro-1,2,2,2-tetrafluoroethyl trifluoromethyl (9CI) (CA INDEX NAME)

60901-73-7 CAPLUS Peroxide, 2-fluoroethyl trifluoromethyl (9CI) (CA INDEX NAME)

F3C-0-0-CH2-CH2F

60901-74-8 CAPLUS Propane, 1,1,1,2,3,3,3-heptafluoro-2-(trifluoromethoxy)- (9CI) (CA INDEX NAME)

60901-75-9 CAPLUS Peroxide, 1,2,2,2-tetrafluoro-1-(trifluoromethyl)ethyl trifluoromethyl (SCI) (CA INDEX NAME)

60901-76-0 CAPLUS Peroxide, heptafluoropropyl trifluoromethyl (9CI) (CA INDEX NAME)

F3C-0-0-CF2-CF2-CF3

60901-77-1 CAPLUS Peroxide, nonafluorocyclopentyl trifluoromethyl (9CI) (CA INDEX NAME)

## 09961347 Page 51 09/09/2002

L29 ANSWER 10 OF 16 CAPLUS COPYRIGHT 2002 ACS (Continued)

ΙŤ 34511-13-2

AGENTALS AGE (Reactant)
(reaction of, with alkenes)
34511-13-2 CAPLUS
Peroxyhypofluorous acid, trifluoromethyl ester (9CI) (CA INDEX NAME)

F3C-0-0-F

L29 ANSWER 11 OF 16 CAPLUS COPYRIGHT 2002 ACS (Continued) F3C-0-CF2-CC12-F 25957-33-9 CAPLUS Ethane, 2-chloro-1,1-difluoro-1-(trifluoromethoxy)- (9CI) (CA INDEX NAME) F3C-0-CF2-CH2C1 54362-30-0 CAPLUS Peroxide, 2-chloroethyl trifluoromethyl (9CI) (CA INDEX NAME) F3C-0-0-CH2-CH2C1 54362-31-1 CAPLUS Peroxide, 2-chloro-1,1,2,2-tetrafluoroethyl trifluoromethyl (9CI) (CA INDEX NAME) F3C-0-0-CF2-CF2-C1 54362-32-2 CAPLUS Peroxide, 2,2-dichloro-1,1,2-trifluoroethyl trifluoromethyl (9CI) (CA INDEX NAME) F3C-0-0-CF2-CCl2-F 54362-33-3 CAPLUS Peroxide, 2,2,2-trichloro-1,1-difluoroethyl trifluoromethyl (9CI) (CA INDEX NAME) F3C-0-0-CF2-CC13 \$4362-34-4 CAPLUS Ethane, 1,1,1-trichloro-2,2-difluoro-2-(trifluoromethoxy)- (9CI) (CA INDEX NAME) FaC-0-CF2-CC13 S4162-35-5 CAPLUS
Peroxide, 2-chloro-1,1-difluoroethyl trifluoromethyl (9CI) (CA INDEX NAME)

Examiner Anderson 703-605-1157

F3C-0-0-CF2-CH2C1 RN 54362-36-6 CAPLUS ACCESSION NUMBER: 1975:72506 CAPLUS
DOCUMENT NUMBER: 1975:72506 CAPLUS
DOCUMENT NUMBER: 82:72506
TITLE: Direct synthesis of fluorocarbon peroxides. III. Addition of chloroperoxytrifluoromethane to olefins

AUTHOR(S): Walker, Nyal) DebMarteau, Darryl D.
CORPORATE SOURCE: Dep. Chem., Kansas State Univ., Manhattan, Kans., USA
SOURCE: CODEN: JACSAT

DOCUMENT TYPE: Journal
LANGUAGE: Beglish
AB C7300Cl added to olefins to give trifluoromethyl-peroxy derivs. in high yield. The reactions were unidirectional and proceeded by an electrophilic mechanism, in which the positive chlorine of C7300Cl adds to the carbon with the greatest no. of hydrogens or the fewest fluorines. Reactions with C2H4, C2F4, C2F3Cl, CF2:CCl2, CF2:CCl2, CFH:CCR1, and cis-CFH:CFH. Occurred readily >0.degree:, perfluoropropene and perfluoro-cyclopentene were unreactive under all conditions tried. With 13755-26-3

RL: RCT (Reactant) (addn. reaction with olefins)

N3 2755-26-3 CAPLUS RL: RCT (Reactant)
(addn. reaction with olefins)
32755-26-3 CAPLUS
Peroxyhypochlorous acid, trifluoromethyl ester (8CI, 9CI) (CA INDEX NAME) F3C-0-0-C1 1561-50-8P 1645-95-0P 25476-71-5P 25937-33-9P 54362-30-0P 54362-31-1P 54362-32-2P 54362-33-3P 54362-34-4P 54362-35-5P 54362-33-6P 54362-34-7P 54362-38-8P 54362-39-9P RL: SPN (Synthetic preparation); PREP (Preparation) (prepn. of)
1561-50-8 CAPUS
Ethane, 1-chloro-1,1,2,2-tetrafluoro-2-(trifluoromethoxy)- (9CI) (CA
INDEX NAME) F3C-0-CF2-CF2-C1 RN 1645-95-0 CAPLUS CN Ethane, 1-chloro-2-(trifluoromethoxy)- (9CI) (CA INDEX NAME) F3C-0-CH2-CH2C1 25476-71-5 CAPLUS Ethane, 1,1-dichloro-1,2,2-trifluoro-2-(trifluoromethoxy)- (9CI) (CA INDEX NAME)

L29 ANSWER 11 OF 16 CAPLUS COPYRIGHT 2002 ACS (Continued) (CN Peroxide, 2,2-dichloro-1-fluoroethyl trifluoromethyl (9CI) (CA INDEX NAME)

F3C-0-0-CH-CHC12

54362-37-7 CAPLUS Ethane, 1,1-dichloro-2-fluoro-2-(trifluoromethoxy)- (9CI) (CA INDEX NAME)

F3C-O-CH-CHCl2

54362-38-8 CAPLUS Peroxide, 2-chloro-1,2-difluoroethyl trifluoromethyl (9CI) (CA INDEX NAME)

F C1

54362-39-9 CAPLUS Ethane, 1-chloro-1,2-difluoro-2-(trifluoromethoxy)- (9CI) (CA INDEX NAME)

F C1 | | F3C-O-CH-CH-F

RE: RCT (Reactant)
(reaction of, with chlorine fluoride)
16118-40-4 CAPLUS
Carbonofluoridoperoxoic acid, trifluoromethyl ester (9CI) (CA INDEX NAME)

F-C-O-O-CF3

### 09961347 Page 52 09/09/2002

L29 ANSWER 12 OF 16 CAPLUS COPYRIGHT 2002 ACS ACCESSION NUMBER: 1975:50798 CAPLUS DOCUMENT NUMBER: 82:50798 TITLE: 82:50798

AUTHOR(5):

82:50798
Halogen perchlorates. Reactions with
fluorocarbon halides
Schack, Carl J., Filipovich, Don; Christe, Karl O.
Rocketdyne Div., Rockwell Int., Canoga Park, Calif.,
USA CORPORATE SOURCE:

SOURCE:

Inorg. Chem. (1975), 14(1), 145-51 CODEN: INOCAJ

DOCUMENT TYPE:

inorg. Chem. (1975), 14(1), 145-51
CODEM: INOCAJ
JOURNAT
SUAGE:
JOURNAT
SUAGE:
English
The reactions of XC104 (X - Cl, Br) with numerous fluoroalkyl halides were examined. For fluorocarbon iodides, these reactions generally produced high yields of the novel fluorocarbon perchlorates
CF3C104, CF3CF2C104, n-CF715C104, O4C1CF2CF2C104, and ICF2CF2C104.
Important insight into the mechanism of formation of these compds. was obtained through the isolation of complex intermediates such as (CF3)2CF1(C104)2 and n-CF715IC(C104)2. Based on their vibrational spectra, these intermediates have the ionic structure [Rf]2I]+[I(C104)4]-. Fluorocarbon bromides reacted less readily but sometimes did produce perchlorate derivs. such as (O4C1CF2CFB1)2, CF3CFBCF2C104, and BrCF2CF2C2C104. Neither mono nor di, primary nor secondary Cl contained in satd. RfC1 materials interacted with these helogen perchlorates.
These and other related reactions are discussed and characteristic data are given for this new and interesting class of compds.
\$2003-43-99
RL: SNN (Synthetic preparation); PREF (Preparation)

RL: SPN (Synthetic preparation); PREP (Preparation) (prepn. of) 52003-45-9 CAPLUS Perchloric acid, trifluoromethyl ester (9CI) (CA INDEX NAME)

L29 ANSWER 13 OF 16 CAPLUS COPYRIGHT 2002 ACS (Continued)

42028-66-0 CAPLUS Peroxide, 1-chloro-1,2,2-trifluoro-2-(trifluoromethoxy)ethyl trifluoromethyl (9CI) (CA INDEX NAME)

50921-20-5 CAPLUS
Butane, dichlorohexafluoro-1,4-bis(trifluoromethoxy)- (9CI) (CA INDEX NAME)

F3C-0-(CH2)4-0-CF3

2 (D1-C1)

6 (D1-F)

RN 50921-48-7 CAPLUS
CN Peroxide, 2-(trifluoromethoxy)ethyl trifluoromethyl (9CI) (CA INDEX NAME)

F3C-O-CH2-CH2-O-O-CF3

50921-49-8 CAPLUS Peroxide, 1,1,2,2-tetrafluoro-Z-(trifluoromethoxy)ethyl trifluoromethyl (SCI) (CA INDEX NAME)

F3C-O-CF2-CF2-O-O-CF3

S0921-50-1 CAPLUS
Peroxide, 1,4-dichioro-1,2,2,3,3,4-hexafluoro-4-(trifluoromethoxy)butyl
trifluoromethyl (9CI) (CA INDEX NAME)

L29 ANSWER 13 OF 16 CAPLUS COPYRIGHT 2002 ACS
ACCESSION NUMBER: 1974:403295 CAPLUS
DOCUMENT NUMBER: 81:3295
TITLE: Direct synthesis of fluorocarbon peroxides. I. Addition of bis(trifluoromethyl) trioxide to selected carbon-carbon multiple bonds
AUTHOR(S): Hohorst, Frederick A.: Paukstelis, Joseph V.;
DeMARteau, Darryl D.
CORPORATE SOURCE: Dep. Chem., Kansas State Univ., Manhattan, Kans., USA SOURCE: J. O.g. Chem. (1974), 39(9), 1298-1302
CODEN: JOCEAN
DOCUMENT TYPE: Journal
LANGUAGE: Begitsh
AB The addn. of bis(trifluoromethyl) trioxide, CF3000CF3, to a variety of C-C multiple bonds is reported. With ethylene, tetrafluoroethylene, chlorotrifluoroethylene hexafluoropropylene, perfluorobutene-2, and perfluorocotribuene hexafluoropropylene, perfluorobutene-2, and perfluorocotrylene hexafluoropropylene, Defluorobutene-2, and cF30CRRICRAR300CF3. These products form in 50-804 yield with alkenes which are not prone to radical polymn. In the case of tetrafluoroethylene and chlorotrifluoroethylene, addnl. products contg. two mol. of alkene are obdd. as well as several trifluoromethyl ethers. The proposed reaction mechanism of initial addn. of CF30.bul. to the alkene is consistent with the obdd. products.

the obsd. products. 1718-18-9 RL: RCT (Reactant)

RL: RCT (Reactant)
(addn. reaction of, with alkenes)
1718-18-9 CAPLUS
Trioxide, bis(trifluoromethyl) (8CI, 9CI) (CA INDEX NAME)

F3C-0-0-0-CF3

39479-36-2P 42028-65-9P 42028-66-0P 50921-20-5P 50921-48-7P 50921-49-8P 50921-50-1P 50921-51-2P 50921-52-3P 50921-53-4P 50921-54-5P 50921-55-6P 50921-57-6P 50921-74-9P 50921-75-0P 50921-76-1P 50921-77-2P

RL: SPN (Synthetic preparation); PREP (Preparation)

(prepn. of)
39479-36-2 CAPLUS
Butane, 1,1,2,2,3,3,4,4-octafluoro-1,4-bis(trifluoromethoxy)- (9CI) (CA
INDEX NAME)

F3C-O-(CF2)4-O-CF3

42028-65-9 CAPLUS
Peroxide, 2-chloro-1,1,2-trifluoro-2-(trifluoromethoxy)ethyl
trifluoromethyl (9CI) (CA INDEX NAME)

L29 ANSWER 13 OF 16 CAPLUS COPYRIGHT 2002 ACS (Continued)

50921-51-2 CAPLUS
Peroxide, 1,3-dichloro-1,2,2,3,4,4-hexafluoro-4-(trifluoromethoxy)butyl
trifluoromethyl (9C1) (CA INDEX NAME)

50921-52-3 CAPLUS
Peroxide, 1-[difluoro(trifluoromethoxy)methyl]-1,2,2,2-tetrafluoroethyl
trifluoromethyl (9CI) (CA INDEX NAME)

50921-53-4 CAPLUS
Peroxide, 1,1,2,3,3,3-hexafluoro-2-(trifluoromethoxy)propyl
trifluoromethyl (9CI) (CA INDEX NAME)

50921-54-5 CAPLUS 2-Butanone, 1,1,1,4,4,4-hexafluoro-3,3-bis(trifluoromethoxy)- (9CI) (CA INDEX NAME)

50921-55-6 CAPLUS
2-Butanone, 1,1,1,4,4,4-hexafluoro-3-(trifluoromethoxy)-3[(trifluoromethyl)dioxy]- (9CI) (CA INDEX NAME)

L29 ANSWER 13 OF 16 CAPLUS COPYRIGHT 2002 ACS (Continued)

C- CF3 0- CF3

S0921-57-8 CAPLUS
Peroxide, 1,1,2,2,3,3,4,4-octafluoro-4-(trifluoromethoxy)ethyl
trifluoromethyl (9CI) (CA INDEX NAME)

F3C-0-(CF2)4-0-0-CF3

50921-74-9 CAPLUS
Peroxide, 1,2,3,3,3-pentafluoro-2-(trifluoromethoxy)-1(trifluoromethyl)ethyl trifluoromethyl, [S-(R\*,S\*)]- (9CI) (CA INDEX NAME)

Absolute stereochemistry.

50921-75-0 CAPLUS Peroxide, 1,2,3,3,3-pentafluoro-2-(trifluoromethoxy)-1-(trifluoromethyl)ethyl trifluoromethyl,  $\{S-(R^*,R^*)\}-(9CI)$  (CA INDEX NAME)

Absolute stereochemistry.

50921-76-1 CAPLUS Pecoxide, 1,2,2,3,3,4,4,5-octafluoro-5-(trifluoromethoxy)cyclopentyl trifluoromethyl, cis- (9CI) (CA INDEX NAME)

L29 ANSWER 14 OF 16 CAPLUS COPYRIGHT 2002 ACS ACCESSION NUMBER: 1973:478017 CAPLUS DOCUMENT NUMBER: 79:78017 Direct synthesis of flue

79:78017
Direct synthesis of fluorocarbon
peroxides. Addition of bis(trifluoromethyl)
trioxide to chlorotrifluoroethylene
Hohorst, Frederick A., DesMarteau, Darryl D.
Dep. Chem., Kans. State Univ., Manhattan, Kans., USA
J. Chem. Soc., Chem. Commun. (1973), (12), 110873
CODEN: JCCCAT CORPORATE SOURCE: SOURCE:

DOCUMENT TYPE:

COURT SOCIAL

SENT TYPE: Journal

JAGE: English

Addn. of CF3000CF3 to F2C:CFC1 at 70.degree. gave a mixt. contg.

CF300CF2CFC10CF3 and CF30CF2CFC100CF3. The structures were confirmed by

19F NMR. 42028-65-9P 42028-66-0P

RL: SPN (Synthetic preparation); PREP (Preparation) (preph. of) 42028-65-9 CAPLUS Peroxide, 2-chloro-1,1,2-trifluoro-2-(trifluoromethoxy)ethyl trifluoromethyl (SCI) (CA INDEX NAME)

42028-66-0 CAPLUS
Peroxide, 1-chloro-1,2,2-trifluoro-2-(trifluoromethoxy)ethyl
trifluoromethyl (9CI) (CA INDEX NAME)

F<sub>3</sub>C-0-0-C-CF<sub>2</sub>-0-CF<sub>3</sub>

1718-18-9
RL: RCT (Reactant)
(reaction of, with chlorotrifluoroethylene)
1718-18-9 CAPLUS

Trioxide, bis(trifluoromethyl) (8CI, 9CI) (CA INDEX NAME)

F1C-0-0-0-CF1

L29 ANSWER 13 OF 16 CAPLUS COPYRIGHT 2002 ACS (Continued) Relative stereochemistry

50921-77-2 CAPLUS Peroxide, 1,2,2,3,3,4,4,5-octafluoro-5-(trifluoromethoxy) cyclopentyl trifluoromethyl, trans- (9CI) (CA INDEX NAME)

Relative stereochemistry.

L29 ANSWER 15 OF 16
ACCESSION NUMBER:
DOCUMENT NUMBER:
TITLE:
INVENTOR(S):
PATENT ASSIGNEE(S):
SOURCE:
OUTCOMENT TYPE:

COCIMENT TYPE:
CAPLUS COPYRIGHT 2002 ACS
1969:67606 CAPLUS
70:67606
Perfluoroalkyleroxy perfluoroalkylfluoroxy compounds
Perfluoroalkyleroxy perfluoroalkylfluoroxy compounds
Perfluoroalkyleroxy perfluoroalkylfluoroxy compounds
OUTCOMENT TYPE:

COCIMENT TYPE:

CAPLUS COPYRIGHT 2002 ACS
70:67606 CAPLUS
70:67606

DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO. KIND DATE APPLICATION NO. DATE

US 3420866 A 19690107 US 1966-614375 19661212

CF3CO2NO (1 g.) in a stainless steel tray was placed in a 450-ml. Cu
vessel, the vessel cooled to -20.degree. and flushed with N, and the
contents treated with 34 F in N at 0.02 ft.3/min. 7 hrs. The off gases
were passed through a trap immersed in liq. air; the contents of the trap
fractionated through traps at -78.degree., -119.degree., and -196.degree.;
and the contents of the -196.degree. traps sepd. by gas chromatog. to give
164 C2F5OF (1). Similarly were prepd. (compd. fluorinated and products
given): (CF3)2C(OH)2 (II), (CF3)2CFOF (III); CF3CO2Na (IV), 23% I, 18%
CF3CF(OFT)2 (V), and F2C(OFT)2 (VI); IV, I, V, VI, CZF5OOCF2OF, CF3OOCF2OF,
CZF5OOCF (OFF)CF3, CF3OOCF(OFF)CF3, and (CF3CFOF)202C; EEO)4C, I);
(CF3)3CONa, (CF3)3CONF, CSF11CO2Na, perfluorohexyloxyfluorides; ClCF2CO2Na,
CLCF2CF2OFF; II Na sait, IV, (CF3)2C(OF)2, I, and V. Other F-contg.
compds. gave similar OF derivs.
18186-37-9P 22410-16-8P

India-3/-9F ZZ410-10-0F
RE: SPN (Synthetic preparation), PREP (Preparation)
(prepn. of)
16156-37-9 CAPUS
Rypoflucrous acid, difluoro[(trifluoromethyl)dioxy)methyl ester (9CI) (CA
INDEX NAME)

F3C-0-0-CF2-0-F

22410-16-8 CAPLUS

Ethanol, tetrafluoro-1-[(trifluoromethyl)dioxy]-, hypofluorite (8CI) (CA INDEX NAME)

```
ACCESSION NUMBER:
1969:402462 CAPLUS
DOCUMENT NUMBER:
1969:402462 CAPLUS
SOURCES
TITLE:
1969:402462 CAPLUS
SOURCES
AUTHOR(S):
AUTHOR(S):
Talbott, Richard L.
CORPORATE SOURCE:
Minnesota Hining and Mfg. Co., Saint Paul, Minn., USA
J. Org. Chem. (1966), 33(5), 2095-9
DOCUMENT TYPE:
DOCUMENT TYPE:
DOLUMENT TY
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L29 ANSWER 16 OF 16 CAPLUS COPYRIGHT 2002 ACS (Continued)
F3C-O-O-CF2-O-F
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=> log y COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	76.29	727.61
DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)	SINCE FILE ENTRY	TOTAL SESSION
CA SUBSCRIBER PRICE	-9.91	-17.34

STN INTERNATIONAL LOGOFF AT 12:01:20 ON 09 SEP 2002



# PALM INTRANET

Day: Monday Date: 9/9/2002 Time: 12:08:12

# **Inventor Name Search Result**

Your Search was:

Last Name = JANIN

First Name = ROBERT

Application#	Patent#	Status	Date Filed	Title	Inventor Name
08608519	6316636	150		SYNTHESIS OF FLUOROCARBON COMPOUNDS	JANIN , ROBERT
09961347	Not Issued	071		SYNTHESIS OF FLUOROCARBON COMPOUNDS	JANIN, ROBERT

Inventor Search Completed: No Records to Display.

Last Name First Name Search Another: Inventor Search ROBERT JANIN

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Day: Monday Date: 9/9/2002 Time: 12:13:00

# **Inventor Name Search Result**

Your Search was:

Last Name = SAINT-JALMES

First Name = LAURENT

Application#	Patent#	Status	Date Filed	Title	Inventor Name
09171990	6201149	150	01/19/1999	ORGANIC BASE HYDROGENOFLUOROSULPHONATES, THEIR USE IN RELEASING ORGANIC BASES FROM THEIR FLUOROHYDRATE, METHOD OF PREPARATION THEREOF, COMPOUND CONTAINING THEM	SAINT- JALMES , LAURENT
09180598	6166271	150	01/19/1999		SAINT- JALMES , LAURENT
09012232	Not Issued	161	01/23/1998	REAGENT AND PROCESS WHICH ARE USEFUL FOR GRAFTING A SUBSTITUTED DIFLUOROMETHYL GROUP ONTO A COMPOUND CONTAINING AT LEAST ONE ELECTROPHILIC FUNCTION	SAINT- JALMES , LAURENT
09230761	6203670	150	04/06/1999	METHOD FOR GRAFTING A SUBSTITUTED DIFLUOROMETHYL GROUP	SAINT- JALMES , LAURENT
08620359	5859288	150	03/22/1996	REAGENT AND PROCESS FOR THE SYNTHESIS OF OXYSULPHIDE- CONTAINING FLUORINE- CONTAINING ORGANIC DERIVATIVES	SAINT- JALMES , LAURENT
08620348	5756849	150	:		SAINT- JALMES , LAURENT
08608519	6316636	150	02/28/1996	SYNTHESIS OF FLUOROCARBON COMPOUNDS	SAINT- JALMES , LAURENT

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09201854	Not Issued	094		REAGENT AND PROCESS WHICH ARE USEFUL FOR GRAFTING A SUBSTITUTED DIFLUOROMETHYL GROUP ONTO A COMPOUND CONTAINING AT LEAST ONE ELECTROPHILIC FUNCTION	SAINT- JALMES , LAURENT
09308257	6203721	150	07/19/1999	COMPOUNDS USEFUL FOR PERHALOGENOALKYLATION, REAGENT FOR IMPLEMENTING THESE COMPOUNDS AND SYNTHESIS METHOD FOR OBTAINING THESE COMPOUNDS	SAINT- JALMES , LAURENT
09609216	Not Issued	061	07/05/2000	EXCHANGE AND TO THE RELEASE OF AN AMINE FROM ITS CARBAMOYL FLUORIDE	SAINT- JALMES, LAURENT
10019694	Not Issued	030	05/03/2002	METHOD FOR DEHYDROGENOFLUORINATION OF AN AROMATIC CARBAMOYL FLUORIDE	SAINT- JALMES, LAURENT
09937856	Not Issued	030	01/10/2002	METHOD FOR ACTIVATING MINERAL FLUORIDE IN AN ORGANIC MEDIUM	SAINT- JALMES, LAURENT
09937853	Not Issued	020	01/10/2002	METHOD FOR ACTIVATING AROMATIC SUBSTRATES BY MICROWAVES	SAINT- JALMES, LAURENT
09961347	Not Issued	071	09/25/2001	SYNTHESIS OF FLUOROCARBON COMPOUNDS	SAINT- JALMES, LAURENT
09786665	Not Issued	093		METHOD FOR CONDENSATION OF AROMATIC DERIVATIVE(S) AND A SULPHINIC DERIVATIVE	SAINT- JALMES, LAURENT
09768604	6388126	150	01/25/2001	ORGANIC BASE HYDROGENOFLUOROSULPHONATES, THEIR USE IN RELEASING ORGANIC BASES FROM THEIR FLUOROHYDRATE, METHOD OF PREPARATION THEREOF, COMPOUND CONTAINING THEM	SAINT- JALMES, LAURENT

Inventor Search Completed: No Records to Display.

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